

U.S. Department of Commerce, Patent and Trademark Office (PTO Form 1449 modified)					Docket No. AMAT/2592.C7/DSM/ LOW K/JW		Serial No. UNKNOWN	
LIST OF PATENTS AND PUBLICATIONS CITED BY APPLICANT					Applicant YAU, et al.		Confirmation No.: UNKNOWN	
(Use several sheets if necessary)					Filing Date		Group	
Examiner UNKNOWN					HEREWITH		UNKNOWN	
U.S. Patent Documents								
Examiner Initial		Document Number	Issue Date	Applicant(s) Name	Class	Subclass	Filing Date If Appropriate	
AL	A1	6,593,655	07/15/2003	Loboda, et al.	257	760	08/14/2000	
AL	A2	6,514,667	02/04/2003	Angelopoulos, et al.	430	271.1	08/17/2001	
AL	A3	6,316,167	11/13/2001	Angelopoulos, et al.	430	313	01/10/2000	
AL	A4	6,287,990	09/11/2001	Cheung, et al.	438	780	09/29/1998	
AL	A5	6,159,871	12/12/2000	Loboda, et al.	438	786	05/29/1998	
AL	A6	6,147,009	11/14/2000	Grill et al.	438	780	06/29/1998	
AL	A7	6,140,226	10/31/2000	Grill et al.	438	637	07/30/1998	
AL	A8	6,124,641	09/26/2000	Matsuura	257	759	12/08/1997	
AL	A9	6,072,227	06/06/2000	Yau et al.	257	642	07/13/1998	
AL	A10	6,068,884	05/30/2000	Rose, et al.	427	255.6	04/28/1998	
AL	A11	6,054,379	04/25/2000	Yau, et al.	438	623	02/11/1998	
AL	A12	6,054,206	04/25/2000	Mountsier	428	312.8	06/22/1998	
AL	A13	6,051,321	04/18/2000	Lee, et al.	428	447	10/24/1997	
AL	A14	5,989,998	11/23/1999	Sugahara, et al.	438	787	06/30/1997	
AL	A15	5,946,593	08/31/1999	Saitoh	438	640	02/20/1996	
AL	A16	5,891,799	04/06/1999	Tsui	438	624	08/18/1997	
AL	A17	5,888,593	03/30/1999	Petrmichl, et al.	427	563	04/12/1996	
AL	A18	5,874,367	02/23/1999	Dobson	438	787	06/30/1993	
AL	A19	5,858,880	01/12/1999	Dobson, et al.	438	758	01/05/1996	
AL	A20	5,834,162	11/10/1998	Malba	430	317	10/28/1996	
AL	A21	5,821,168	10/13/1998	Jain	438	692	07/16/1997	
AL	A22	5,817,572	10/06/1998	Chiang, et al.	438	624	12/18/1996	
AL	A23	5,807,785	09/15/1998	Ravi	438	624	08/02/1996	
AL	A24	5,800,877	09/01/1998	Maeda, et al.	427	535	08/09/1996	
AL	A25	5,739,579	04/14/1998	Chiang, et al.	257	635	09/10/1996	
AL	A26	5,753,364	05/19/1998	Rutherford, et al.	428	355R	01/30/1997	
AL	A27	5,789,319	08/04/1998	Havemann, et al.	438	668	02/26/1996	
AL	A28	5,703,404	12/30/1997	Matsuura	257	758	12/24/1996	
AL	A29	5,700,720	12/23/1997	Hashimoto	438	622	12/20/1995	
Examiner <i>Kevin G. Halderson</i>					Date Considered <i>08/19/2005</i>			
*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with your communication to applicant.								

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RL	A30	5,698,901	12/16/1997	Endo	257	758	09/12/1995	
RL	A31	5,693,563	12/02/1997	Teong	438	627	07/15/1996	
RL	A32	5,683,940	11/04/1997	Yahiro	438	760	12/20/1995	
RL	A33	5,679,413	10/21/1997	Petrmichl, et al.	427	534	10/11/1996	
RL	A34	5,638,251	06/10/1997	Goel, et al.	361	313	10/03/1995	
RL	A35	5,637,351	06/10/1997	O'Neal, et al.	427	255.37	05/11/1995	
RL	A36	5,618,619	04/08/1997	Petrmichl, et al.	428	334	03/03/1994	
RL	A37	5,616,369	04/01/1997	Williams, et al.	427	536	06/24/1994	
RL	A38	5,599,740	02/04/1997	Jang, et al.	437	190	11/16/1995	
RL	A39	5,598,027	01/28/1997	Matsuura	257	635	12/21/1995	
RL	A40	5,593,741	01/14/1997	Ikedo	427	579	06/28/1995	
RL	A41	5,578,523	11/16/1996	Fiordalice, et al.	438	633	05/18/1995	
RL	A42	5,563,105	10/08/1996	Dubuzinsky, et al.	438	784	09/09/1994	
RL	A43	5,559,367	09/24/1996	Cohen, et al.	257	77	07/12/1994	
RL	A44	5,554,570	09/10/1996	Maeda, et al.	438	763	01/09/1995	
RL	A45	5,530,581	06/25/1996	Cogan	359	265	05/31/1995	
RL	A46	5,525,550	06/11/1996	Kato	437	238	11/19/1993	
RL	A47	5,508,368	04/16/1996	Knapp, et al.	427	534	03/03/1994	
RL	A48	5,494,712	02/27/1996	Hu, et al.	427	489	11/17/1994	
RL	A49	5,492,736	02/20/1996	Laxman, et al.	427	579	11/28/1994	
RL	A50	5,488,015	01/30/1996	Haveman, et al.	437	195	05/20/1994	
RL	A51	5,468,520	11/21/1995	Williams, et al.	427	560	06/24/1994	
RL	A52	5,465,680	11/14/1995	Loboda	117	84	07/01/1993	
RL	A53	5,364,666	11/15/1994	Williams, et al.	427	579	09/23/1993	
RL	A54	5,362,526	11/08/1994	Wang, et al.	427	573	01/23/1991	
RL	A55	5,360,646	11/01/1994	Morita	427	574	09/01/1993	
RL	A56	5,314,724	05/24/1994	Tsukune, et al.	427	489	08/27/1992	
RL	A57	5,298,587	03/29/1994	Hu, et al.	528	10	12/21/1992	
RL	A58	5,290,736	03/01/1994	Sato, et al.	437	238	09/24/1991	
Examiner <i>Julio J. Maldonado</i>					Date Considered <i>09/17/2005</i>			
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UL	A59	5,284,730	02/08/1994	Takei, et al.	430	66	08/06/1992	
UL	A60	5,279,867	01/18/1994	Friedt, et al.	427	583	07/09/1992	
UL	A61	5,250,473	10/05/1993	Smits	438	790	08/02/1991	
UL	A62	5,246,887	09/21/1993	Yu	438	761	07/10/1991	
UL	A63	5,224,441	07/06/1993	Felts, et al.	118	718	09/27/1991	
UL	A64	5,208,069	05/04/1993	Clark, et al.	427	226	10/28/1991	
UL	A65	5,204,141	04/20/1993	Roberts, et al.	427	255.37	09/18/1991	
UL	A66	5,182,000	01/16/1993	Antonelli, et al.	204	181.1	11/12/1991	
UL	A67	5,156,881	10/20/1992	Okano, et al.	427	572	04/16/1991	
UL	A68	5,124,014	06/23/1992	Foo, et al.	438	694	04/11/1991	
UL	A69	5,120,680	06/09/1992	Foo, et al.	438	789	07/19/1990	
UL	A70	5,093,153	03/03/1992	Brochot, et al.	427	41	02/07/1989	
UL	A71	5,087,959	02/11/1992	Omori, et al.	257	635	03/02/1988	
UL	A72	5,040,046	08/13/1991	Chhabra, et al.	257	635	10/09/1990	
UL	A73	5,028,566	07/02/1991	Legendijk	438	784	07/27/1990	
UL	A74	4,981,724	01/01/1991	Hochberg, et al.	427	255.37	10/28/1977	
UL	A75	4,973,511	11/27/1990	Farmer, et al.	428	216	12/01/1988	
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Examiner Initial		Document Number	Date	Country	Class	Subclass	Translation	
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UL	B1	98/59089	12/30/1998	WO	C23C	16/30	<input type="checkbox"/>	<input checked="" type="checkbox"/>
UL	B2	00/01012	01/06/2000	WO	H01L	23/48	<input type="checkbox"/>	<input checked="" type="checkbox"/>
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<i>Jul</i>	A76	4,900,591	02/13/1990	Bennett, et al.	427	255.17	01/20/1988	
<i>Jul</i>	A77	4,894,352	01/16/1990	Lane, et al.	438	763	10/26/1988	
<i>Jul</i>	A78	4,845,054	07/04/1989	Mitchener	438	790	06/26/1987	
<i>Jul</i>	A79	4,842,888	06/27/1989	Haluska, et al.	427	38	04/07/1988	
<i>Jul</i>	A80	4,828,880	05/09/1989	Jenkins, et al.	427	167	12/21/1987	
<i>Jul</i>	A81	4,824,690	04/25/1989	Heinecke, et al.	427	39	11/03/1987	
<i>Jul</i>	A82	4,812,325	03/14/1989	Ishihara, et al.	427	69	10/21/1986	
<i>Jul</i>	A83	4,798,629	01/17/1989	Wood, et al.	106	287.16	10/22/1987	
<i>Jul</i>	A84	4,789,648	12/06/1988	Chow, et al.	438	633	10/28/1985	
<i>Jul</i>	A85	4,557,946	12/10/1985	Sacher, et al.	427	489	06/03/1983	
<i>Jul</i>	A86	4,168,330	09/18/1979	Kaganowicz	427	39	10/13/1977	
	A87							
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Foreign Patent Documents								
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<i>RA</i>	B26	0 469 926 A1	02/5/1992	EP	C08J	7/06	<input type="checkbox"/>	<input checked="" type="checkbox"/>
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<i>RA</i>	B45	59-222659	12/14/1984	JP (English Abs)	F 16 H	9/18	<input checked="" type="checkbox"/>	<input type="checkbox"/>
<i>RA</i>	B46	199 04 311	01/28/1999	DE	C23C	16/44	<input checked="" type="checkbox"/>	<input type="checkbox"/>
<i>RA</i>	B47	0 849 789	06/24/1998	EP	H01L	21/768	<input type="checkbox"/>	<input checked="" type="checkbox"/>
<i>RA</i>	B48	0 840 365	05/06/1998	EP	H01L	21/311	<input type="checkbox"/>	<input checked="" type="checkbox"/>
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OTHER ART			
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<i>gr</i>	C1	Y.S. Lin, et al. "Plasma Polymerization of Trimethylsilane in Cascade Arc Discharge" Department of Chemical Engineering, and Center for Surface Science and Plasma Technology, University of Missouri-Columbia, 4 February 1997, pg 1653-1665.	
<i>gr</i>	C2	W. D. Brown "Dielectric Material Integration for Microelectronics" Dielectric Science and Technology and Electronics Divisions Proceedings Volume 98-3, 8 pages.	
<i>gr</i>	C3	A. Grill, et al. "Diamondlike Carbon Materials as Low-k Dielectrics" 1997 Materials Research Society, pages 417-423.	
<i>gr</i>	C4	A.M. Wrobel, et al. "Reactivity of Alkylsilanes and Alkylcarbosilanes in Atomic Hydrogen-Induced Chemical Vapor Deposition" Polish Academy of Sciences, Centre of Molecular and Macromolecular Studies, 90-363 Lodz, Poland, pages 1060-1065.	
<i>gr</i>	C5	Laura Peters "Pursuing the Perfect Low-K Dielectric" 64 Semiconductor International, September 1998, 7 pages.	
<i>gr</i>	C6	G. Sugahara, et al. "Low Dielectric Constant Carbon Containing SiO ₂ Films Deposited by PECVD Technique Using a Novel CVD Precursor" February 10-11, 1997 DUMIC Conference, 1997 ISMIC - 222D/97/0019, pg 19-25.	
<i>gr</i>	C7	M.J. Loboda, et al. "Deposition of Low-k Dielectric Films Using Trimethylsilane" Electrochemical Society Proceedings Volume 98-6, pg 145-152.	
<i>gr</i>	C8	S. McClatchie "Low Dielectric Constant Oxide Films Deposited Using CVD Techniques" February 16-17, 1998 DUMIC Conference 1998 IMIC - 333D/98/0311 pg 311-318.	
<i>gr</i>	C9	A. Grill and V. Patel "Low Dielectric Constant Films Prepared by Plasma-enhanced Chemical Vapor Deposition From Tetramethylsilane" IBM-Research Division, T.J. Watson Research Center, Yorktown Heights, New York 10598, pg 3314-3318.	
<i>gr</i>	C10	A. Grill, V. Patel and C. Jahnes "Novel Low-K Dielectrics Based on Diamondlike Carbon Materials" IBM, Research Division, T.J. Watson Research Center, Yorktown Heights, New York 10598, USA, pg 1649 - 1653.	
<i>gr</i>	C11	PCT International Search Report for PCT/US99/02903 Dated August 31, 1999	
<i>gr</i>	C12	C.D. Dobson, A. Kiermasz, K. Beekman, R.J. Wilby, "Advanced SiO ₂ Planarization Using Silane and H ₂ O ₂ ," December 1994, pages 85-87.	
<i>gr</i>	C13	L.C. Feldman, Murray Hill, and W.F. van der Weg, "Applied Surface Science," Volume 43 (1989), pages 4-6.	
<i>gr</i>	C14	"Journal of Vacuum Science & Technology A Vacuum, Surfaces, and Films," J. Vac. Sci. Technol. A, Vol. 13, No. 2, Mar/Apr 1995, pages 475-480.	
<i>gr</i>	C15	M. Matsuura, et al. "Novel Self-planarizing CVD Oxide for Interlayer Dielectric Applications," 1994, pages 5.7.1.-5.7.4.	
<i>gr</i>	C16	Frederic Gaillard, et al. "Silicon dioxide chemical vapor deposition using silane and hydrogen peroxide," J. Vac. Sci. Technol. Jul/Aug 1996, pages 2767-2769.	
<i>gr</i>	C17	"Low Dielectric Constant Insulator Formed by Downstream Plasma CVD at Room Temperature Using TMS/O ₂ ", A. Nara and H.Itoh, Japanese Journal of Applied Physics, Vol. 36. No. 3B (March 1997)	
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LIST OF PATENTS AND PUBLICATIONS CITED BY APPLICANT		Applicant YAU, et al.	Confirmation No.: UNKNOWN
(Use several sheets if necessary)		Filing Date	Group
Examiner UNKNOWN		HEREWITH	UNKNOWN
OTHER ART			
Examiner Initial		Including Author, Title, Date, Pertinent Pages, Etc.	
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fer	C20	S. Sahli et al., "Properties Of Plasma-Polysiloxane Deposited By PECVD", Materials Chemistry and Physics, pp. 106-109, 33 (1993)	
fer	C21	A.M. Wrobel et al., "Oligomeric Products In Plasma-Polymerized Organosilicones", J. Macromol. Sci-Chem., A20 (5&6), pp. 583-618 (1983)	
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Examiner <i>Lucy J. Walden</i>		Date Considered <i>05/17/00</i>	
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Examiner Initial		Including Author, Title, Date, Pertinent Pages, Etc.	
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MR	C45	S. Noguchi, et al., "Liquid Phase Oxidation O Atoms Produced by Microwave Discharge and Si(CH ₃) ₄ ", Extended Abstracts of the 19th Conference on Solid State Devices and Materials, Tokyo, 1987, pages 451-454	
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MR	C49	M.J. Loboda, "Using Trimethylsilane to Improve Safety, Throughput and Versatility in PECVD Processes"; Electrochemical Proceedings Vol. 97-10, Pages 443-453.	
Examiner <i>William J. Maden</i>		Date Considered <i>01/17/2005</i>	
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Sheet 1

of 2

Application Number	10/756,122
Filing Date	JANUARY 13, 2004
First Named Inventor	YAU, ET AL.
Group Art Unit	2823
Examiner Name	JULIO J. MALDONADO
Attorney Docket Number	AMAT/2592.C7/DSM/LOW K/JW
Submission Date	1/14, 2005

U.S. PATENT DOCUMENTS

Examiner Initials*	Cite No. ¹	Document Number	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
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<i>JS</i>	B1	EP 0 849 374 A2	06/24/1998	ICHIMURA	Abstract	
<i>JS</i>	B2	WO 99/63591 A1	12/09/1999	ZHAO, ET AL.	Abstract	
	B3					
	B4					
	B5					
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		Filing Date	JANUARY 13, 2004
		First Named Inventor	YAU, ET AL
		Group Art Unit	2823
		Examiner Name	JULIO J. MALDONADO
		Attorney Docket Number	AMAT/2592.C7/DSM/LOW K/JW
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<i>JJM</i>	C1	European Search Report for EP 01 30 3567, dated November 4, 2004 (AMAT/2592.P3)	
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	C6		
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Examiner <i>Julio J. Maldonado</i>	Date Considered <i>01/17/2005</i>
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